

REMARKS

This application has been carefully reviewed in light of the Office Action dated April 11, 2005. Claims 1 to 3, 5 and 6 are in the application, of which Claim 1 is still the only independent claim. Reconsideration and further examination are respectfully requested.

Replacement sheets are submitted herewith, so as to insert a "Prior Art" legend onto Figures 1 through 5.

An objection was lodged against the disclosure based on language found in Claim 3, and Claim 3 was correspondingly rejected under 35 U.S.C. § 112, second paragraph. Claim 5 was also rejected under 35 U.S.C. § 112, second paragraph. In response, amendments have been made to both claims, such that withdrawal of the objection and rejection is respectfully requested.

Claims 1 and 3 were rejected under 35 U.S.C. § 102(e) over U.S. Patent 6,437,816 (Fujita), Claim 2 was rejected under 35 U.S.C. § 103(a) over Fujita in view of U.S. Patent Application Publication 2001/0050933 (Takahashi); and Claim 5 was rejected over Fujita in view of U.S. Patent 6,798,820 (Okuwaki). It is noted that, in connection with the rejection of Claim 3, a reference was made to the Takahashi publication, and as a consequence the rejection of Claim 3 has been treated as a rejection under § 103(a) and not under § 102(e). Clarification of this matter is respectfully requested if this understanding is not correct. Reconsideration and withdrawal of the rejections are respectfully requested.

The invention concerns a laser exposing apparatus comprising first and second laser sources emitting respective first and second laser beams, with the second laser beam having a wavelength shorter than that of the first laser beam. According to one aspect of the invention, adjustment means are provided for selectable adjustment of respective optical path lengths of the first and second laser beams. The optical path length of the first laser beam is set to be relatively shorter than the optical path length of the second laser beam which is set to be relatively longer.

By virtue of the foregoing arrangement, wherein the path lengths are selectively adjustable as set out in the claims, it is possible to avoid situations in which there are differences in magnifications of image formation due to the differences in wavelengths between the two laser beams.

Fujita describes a delay correction optical system 120 shown in Figure 4, having a structure in which the optical path length of the laser beam of a shorter wavelength is longer than the optical path length of the laser beam having a longer wavelength. The delay correction optical system 120 acts so that the exposure of a second laser beam with respect to a first laser beam is delayed so as to superimpose the first and second laser beams on drum surface 111.

The Office Action equates Fujita's delay correction optical system 120 with the adjustment means of the present invention. Applicant respectfully submits that such a correspondence is misplaced, since Fujita's delay correction optical system 120 does not provide for "selectable adjustment" as in the adjustment means of the present invention. In particular, Fujita's delay correction optical system 120 is comprised of two reflection

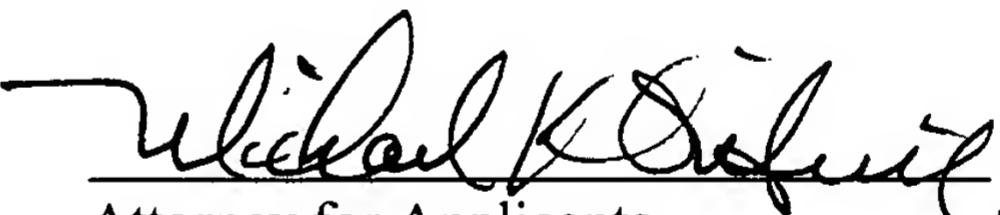
mirrors 121 and 122 arranged in parallel with each other, such that the path length difference between Fujita's first and second lasers is not "adjustable" and is certainly not capable of "selectable adjustment".

The references to Takahashi and Okuwaki have both been reviewed, but they are not seen to add anything to the above-noted deficiencies of Fujita. In particular, neither reference is seen to disclose or to suggest adjustment means for selectable adjustment of respective optical path lengths of first and second laser beams, as set out in Claim 1 herein.

It is therefore respectfully submitted that Claim 1 is fully in condition for allowance, and such action is courteously solicited.

Applicant's undersigned attorney may be reached in our Costa Mesa, California office at (714) 540-8700. All correspondence should continue to be directed to our below-listed address.

Respectfully submitted,



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